

RESPONSE UNDER 37 C.F.R. § 1.116  
EXPEDITED PROCEDURE  
EXAMINING GROUP 2800

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants: Gabric, *et al.* Docket No.: INF 2006 VJ 33543 US

Serial No.: 10/586,788 Art Unit: 2893

Filed: September 2, 2008 Examiner: Nikolay K. Yushin

Conf. No.: 1598

For: Plasma Excited Chemical Vapor Deposition Method  
Silicon/Oxygen/Nitrogen-Containing-Material and Layered Assembly

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Do not enter  
/NY/

**RESPONSE UNDER 37 CFR § 1.116**

Dear Sir:

Applicants respectfully submit the following amendments and remarks in response to Examiner's Office Action dated November 4, 2009, which Action is made final. Applicants respectfully request that these amendments and remarks be entered pursuant to the provisions of 37 CFR § 1.116, and respectfully request reconsideration of claims 21-36, and 38.